

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Mitsutoshi MIYASAKA

Application No.: 09/885,027

Filed: June 21, 2001

For:

Group Art Unit: 2815

Examiner:

J. Jackso

36654.04 Docket No.:

THE THIN FILM SEMICONDUCTOR DEVICE ITSELF, LIQUID CRYSTAL DISPLAY, AND ELECTRONIC DEVICE

## AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

In reply to the August 20, 2002 Office Action, the period for reply extended to January 21, 2003, by a Petition for Extension Time, filed herewith, please amend the aboveidentified application as follows:

## IN THE CLAIMS:

## Please replace claims 1 and 2 as follows:

1. (Amended) A thin film semiconductor device, comprising:

a substrate;

an underlevel protection layer formed over the substrate and including a

plurality of films, at least one of which includes a silicon oxide; and

a crystallized semiconductor layer in contact with the film including the silicon oxide, wherein the crystallized semiconductor layer forms an active layer of a transistor,

an effective doping concentration of the crystallized semiconductor layer figuring 1x 10<sup>18</sup> cm<sup>-3</sup> or less and the crystallized semiconductor layer having the thickness of